

**What is claimed is:**

1. A method of exposure error adjustment in photolithography for multiple products, comprising the steps of:

- 5        choosing a photo feedback system (PFBS);  
         providing a standard point;  
         providing a compensation difference; and  
         calculating a photo feedback system (PFBS) parameter to evaluate an adjustment value of each operation for automatic adjustment.

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2. The method of claim 1, wherein the step of choosing the photo feedback system (PFBS) is a decision of the photo feedback system (PFBS) suited to a host product or a miscellaneous product.

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3. The method of claim 2, wherein the standard point for the host product is the photo feedback system (PFBS) parameter of the host product last processed.

4. The method of claim 2, wherein the compensation difference for the host product is an actual exposure error of the host product last processed.

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5. The method of claim 2, wherein the standard point for the miscellaneous product is the photo feedback system (PFBS) parameter of the host product in a nearest operation.

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6. The method of claim 2, wherein the compensation difference for the

miscellaneous product comprises a difference between the host product and the miscellaneous product and the actual error of the miscellaneous product last processed.

7. The method of claim 6, wherein the difference between the host product and the  
5 miscellaneous product is a value difference in the photo feedback system (PFBS) parameter between the miscellaneous product last processed and the host product in the nearest operation.

8. A method of exposure deviation error adjustment for multiple products,  
10 comprising the steps of:

choosing a photo feedback system (PFBS) suited to a host product or a miscellaneous product;

providing a photo feed-back system (PFBS) parameter evaluated from the host product in a nearest operation as a standard point;

15 providing a compensation difference; and

calculating the photo feedback system (PFBS) parameter to evaluate an adjustment deviation of each exposure operation for automatic adjustment.

9. The method of claim 8, wherein the photo feedback system (PFBS) parameter  
20 is the adjustment deviation.

10. The method of claim 8, wherein the compensation difference for the host product is an actual deviation error of the host product last processed.

25 11. The method of claim 8, wherein the compensation difference for the

miscellaneous product comprises a difference between the host product and the miscellaneous product and the actual deviation error of the miscellaneous product last processed.

5        12. The method of claim 11, wherein the difference between the host product and the miscellaneous product is a value difference in the photo feedback system (PFBS) parameter between the miscellaneous product last processed and the host product in the nearest operation.

10       13. A method of exposure critical dimension (CD) loss adjustment for multi-product, comprising the steps of:

choosing a photo feedback system (PFBS) suited to a host product or a miscellaneous product;

15       providing a photo feed-back system (PFBS) parameter evaluated from the host product in a nearest operation as a standard point;

providing a compensation difference; and

calculating the photo feedback system (PFBS) parameter to evaluate an adjustment critical dimension (CD) of each exposure operation for automatic adjustment.

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14. The method of claim 13, wherein the photo feedback system (PFBS) parameter is the adjustment critical dimension (CD).

25       15. The method of claim 13, wherein the compensation difference for the host product is an actual critical dimension (CD) loss of the host product last processed.

16. The method of claim 13, wherein the compensation difference for the miscellaneous product comprises a difference between the host product and the miscellaneous product and the actual critical dimension (CD) loss of the miscellaneous product last processed.

17. The method of claim 16, wherein the difference between the host product and the miscellaneous product is a value difference in the photo feedback system (PFBS) parameter between the miscellaneous product last processed and the host product in the nearest operation.